

Title (en)

METHOD AND DEVICE FOR DRYING PHOTORESIST COATINGS

Title (de)

VERFAHREN UND VORRICHTUNG ZUR TROCKNUNG VON PHOTORESISTSCHICHTEN

Title (fr)

PROCEDE ET DISPOSITIF DE SECHAGE DE COUCHES PHOTORESISTANTES

Publication

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Application

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Abstract (en)

[origin: WO9959191A2] The present invention relates to a method and device for drying photoresist coatings. A substrate (12) provided with the photoresist coating is impinged upon by infrared radiation from an infrared radiation source (4) with an adjustable output. The temperature of the area around the photresist layer is measured during drying. The output of the infrared radiation source is temperature-controlled so as to achieve a specific chronological temperature cycle. For this purpose, the inventive device is provided with a control unit (8) and a temperature measuring device (6, 7). The inventive method and device pertaining thereto enable especially thick photoresist coatings ($\geq 20 \mu\text{m}$) to be dried in an optimum manner over a short period of time. The photoresist mask that is subsequently produced has a high resolution.

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